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**ABSTRACT OF THE DISCLOSURE**

5           An apparatus for removing fluorinated and chlorinated  
compounds contained in waste gas streams from semiconductor  
etch and deposition processes. The apparatus has a  
treatment chamber in which a plurality of liquid films are  
10           formed to absorb the fluorinated and chlorinated compounds  
contained in the waste gas streams that pass through the  
liquid films. The apparatus includes a tank for receiving  
the mixture of the absorbed fluorinated and chlorinated  
compounds and the liquid, and a dehumidifying device for  
15           stabilizing and dehumidifying the humidified waste gas  
streams.